

Dependence of Electrical and Optical Properties of Sol-gel-derived SnO₂ Thin Films on Sb-substitution

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In the present work, Sb-doped SnO₂ (ATO) thin films were deposited on Si substrates by spin-coating method and the influence of Sb-doping on surface roughness, structural, optical and electrical properties has been investigated. AFM measurements show that the surface roughness decreases with increasing the Sb-doping concentration up to 5 mol%. XRD results confirm that all prepared ATO films have a tetragonal rutile structure of tin oxide. It has been observed that both the crystallite size and the extinction coefficient decrease with increasing Sb-doping concentration up to 5 mol%, while the refractive index increases with increasing Sb-doping concentration. The electrical resistivity decreases with increasing Sb-doping concentration, and the lowest resistivity obtained is $8.5 \times 10^{-3} \Omega \cdot \text{cm}$ for SnO₂ doped with 7.5 mol% of Sb.

Keywords: SnO₂ thin films, spin-coating, optical constants, resistivity.

1. INTRODUCTION

In recent years, tin oxide (SnO₂) thin films received much attention due to their combination of a wide band-gap energy of 3.6 eV at 300 K [1–4], unique electrical and optical properties. This allows SnO₂ thin films to be considered as important transparent conductive oxide (TCO) films with potential applications in optoelectronic devices [5–8], gas sensors [4, 5, 9], dye sensitized solar cells [10], and lithium-ion batteries [11, 12]. Undoped tin oxide possesses a low conductivity leading to high electrical resistivity and this prevents it from commercial applications [13]. To meet the market demands of SnO₂ thin films, a large variety of metals or ions can be doped into SnO₂ thin films to improve both optical and electrical properties [13–15]. Among different dopants, antimony (Sb) appears to be a suitable dopant for SnO₂ since the substitution of Sn⁴⁺ by Sb⁵⁺ into SnO₂ lattice highly improves the n-type semiconductor characteristics of SnO₂ [14, 16]. Furthermore, antimony doped tin oxide (ATO) thin films are transparent conductive oxide (TCO) films seeing that they combine excellent electrical properties, high transparency in visible region and chemical stability [14, 17–19]. Therefore, it is very significant to prepare ATO thin films for a broad series of applications.

Currently, ATO thin films have been prepared by different methods including electro-deposition and dip-coating [20], sputtering techniques [13, 16, 21], spray ultrasonic method [14, 22], chemical spray pyrolysis technique [23, 24], sol-gel techniques [15, 19, 25, 26], plasma-assisted molecular epitaxy [27]. Compared with other preparation methods, herein, ATO thin films were prepared by sol-gel spin-coating method due to its simplicity, low cost and high effectiveness.

Although there are many research works on physical characterization of ATO thin films, few studies focused on the correlation between Sb doping concentration, resistivity and optical constants of ATO thin films prepared by sol-gel technique. Herein, the optical constants like refractive index and extinction coefficient of ATO films were obtained after model fit of spectroscopic ellipsometry data by using a uniaxial model fit, which has not yet been explored in previous works.

The spectroscopic ellipsometry measurements were performed over a spectrum range of 400–1700 nm and yielded the experimental ellipsometric parameters Ψ and Δ , from which the optical constants and film thicknesses were extracted after a model fit. The refractive index of ATO thin films was found to increase with a corresponding increase in Sb-doping concentration while the extinction coefficient decreased.

2. EXPERIMENTAL DETAILS

2.1. Materials

SnCl₄·5H₂O ≥ 99.0 % and SbCl₃ ≥ 99 % were supplied by Sinopharm Chemical Reagent Co., Ltd; 2-methoxyethanol and ethanolamine were supplied by Tianjin Kaixin Chemical Industry co. LTD. All chemicals were directly used without further purification.

2.2. Sample preparation

ATO thin films were prepared according to the following procedure; 5 mmol of SnCl₄·5H₂O were dissolved in 30 mL of 2-methoxyethanol and then calculated amount of SbCl₃ at a molar ratio varying from 0 to 7.5 mol% were added, followed by addition of few drops of ethanolamine used as a stabilizing agent. The mixture solution was refluxed at 80 °C for 4 hours and after that the obtained suspension was aged for 36 hours to

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ensure its stability and viscosity. ATO films were fabricated on silicon substrates using spin-coating method. The substrates were pre-cleaned by sonication in acetone, isopropanol and in methanol solvents for 10 minutes each, rinsed in deionized water and then dried in an oven at 100 °C for 30 minutes. The solutions were deposited on substrates at a rotating speed of 3000 rpm for 30 sec. After each coating-layer, the films were dried on a hot-plate at 300 °C for 10 minutes to remove the organic residuals and allow the evaporation of the solvent; the coating and drying were repeated for 9 times to obtain the needed thickness. Finally, undoped and Sb-doped SnO₂ thin films were annealed in a tube furnace at 500 °C for 1 hour to improve their crystallinity.

2.3. Characterization

The surface roughness was measured by Atomic Force Microscope (AFM) technique performed on an Asylum Research MFP-3D in a tapping mode, and the film thickness was determined by both scanning electron microscope (SEM) and spectroscopic ellipsometry (SE) measurements. The crystal structure and phase identification were determined by X-ray diffraction (XRD) measurements performed on Philips X'PertPro with Cu K α radiation ($\lambda = 1.5418 \text{ \AA}$) at a scan rate of 0.03 °/min within 2 θ angle ranging between 20°–80°. The elemental composition and bond states of the films were analyzed by multifunctional X-Ray Photoelectron Spectroscopy (XPS) Kratos AXIS Ultra^{DL}. Spectroscopic ellipsometry measurements were performed for all prepared ATO thin films by Woollam Variable Angle Spectroscopic Ellipsometer (WVASE 32) over a spectral region ranging between 400–1700 nm in a step of 10 nm at two different angles of incidence of 65° and 75° with a step of 10° in order to evaluate the optical constants of the films.

3. RESULTS AND DISCUSSION

3.1. Surface roughness and film thickness

The surface roughness is a key factor to be investigated since it provides a clue about the quality of the optical material under study [28]. From AFM three-dimensional images of Fig. 1, the surface roughness decreases from 0.59 nm for undoped SnO₂ to 0.48, 0.11 and 0.35 nm for ATO film with 2.5, 5.0 and 7.5 mol% of Sb. The ATO film with 5 mol% of Sb doping holds the lowest surface roughness, which is in good agreement with the variation of the crystallite size.

Fig. 2 shows the SEM cross-sectional images for undoped and Sb-doped tin oxide films. The film thickness is found to decrease from 196.1 nm for undoped SnO₂ to 180.4 nm, 178.0 nm and 151.8 nm for ATO with 2.5, 5.0 and 7.5 mol% of Sb; respectively. The difference between the film thicknesses determined from SEM cross-sectional images and those obtained from spectroscopic ellipsometry measurements is trivial and is shown in Table 1.

3.2. Phase and crystallite size analysis

Fig. 3 shows the XRD patterns of the as-prepared ATO thin films, clarifying that the (110), (101), (200), (211), (220), (310) and (301) diffraction peaks are assigned

to the tetragonal rutile structure of SnO₂, (JCPDS Card No 41-1445), with some silicon standard peaks detected from the substrate which are marked with a star in Fig. 3.

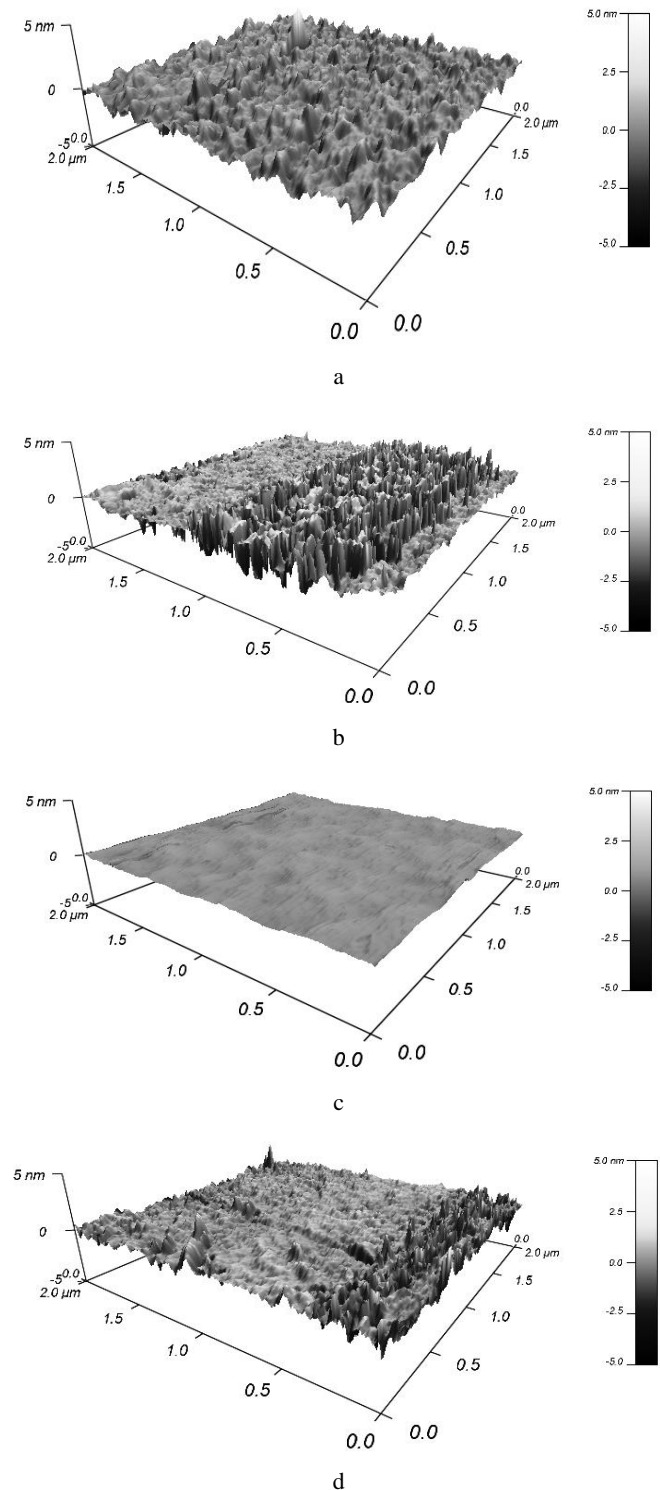


Fig. 1. AFM 3D images of the as-prepared ATO thin films with different Sb-doping concentration a–0 mol% Sb; b–2.5 mol% Sb; c–5.0 mol% Sb; d–7.5 mol% Sb annealed at 500 °C for 1 h

Interestingly, the peak corresponding to (110) reflection is found to be the preferred orientation for the as-prepared ATO films and this is in consistency with literature [13, 26, 29, 30].

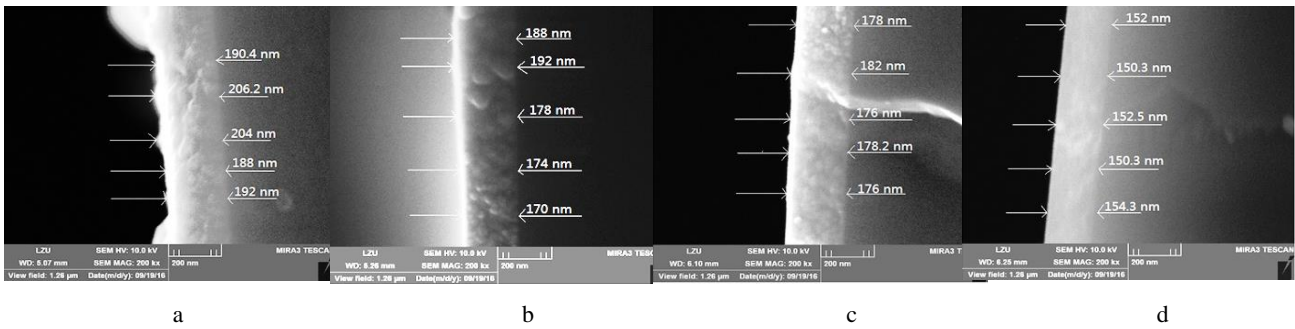


Fig. 2. SEM cross-sectional images: a – SnO₂; b – ATO-2.5; c – ATO-5.0; d – ATO-7.5

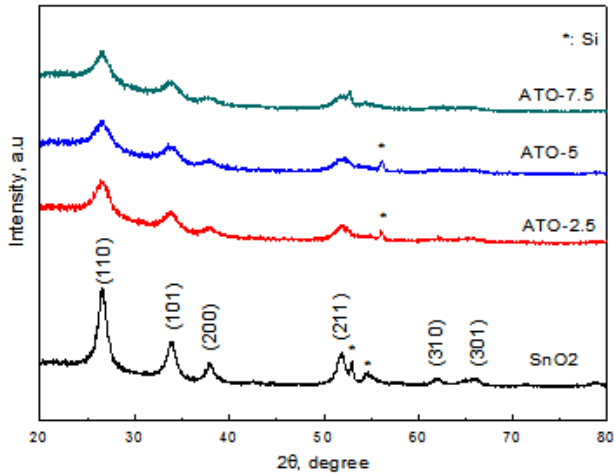


Fig. 3. XRD patterns of the as-prepared ATO films with different Sb-doping concentrations, all films were annealed at 500 °C for 1 h

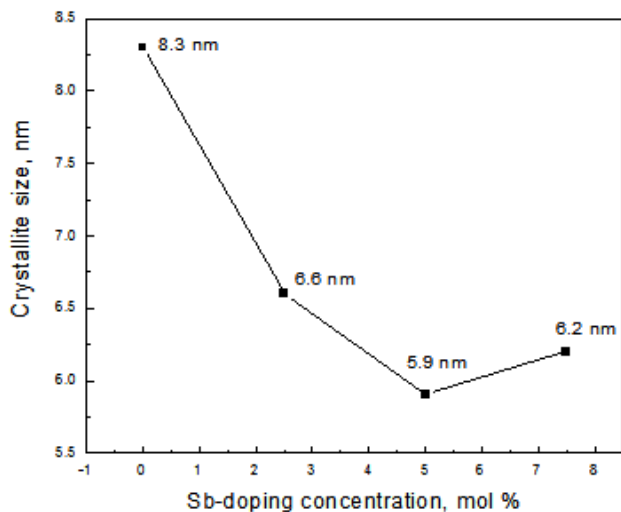


Fig. 4. Variation of the crystallite size of ATO thin films as a function of Sb-doping concentration

It can be clearly observed that after Sb incorporation, some weak diffraction peaks disappear and others become wider and their intensities become lower due to grain size reduction and lattice distortion confirming the incorporation of Sb⁵⁺ into SnO₂ lattice. Fig. 4 shows the variation of the crystallite size estimated from XRD data using MDI Jade software. The crystallite size decreases from 8.3 nm for undoped SnO₂ to 6.6, 5.9 nm for ATO

with 2.5, 5.0 mol% of Sb, respectively as illustrated in Fig. 4. However, when the doping concentration increases to 7.5 mol%, a small increase (0.3 nm) in crystallite size is observed compared to 5 mol%.

By considering the obtained AFM results and the estimated crystallite sizes, we can conclude that the optimum Sb-doping concentration is 5 mol%. The doped Sb could substitute Sn in ATO film efficiently up to 5 mol% concentration. When the doping concentration greater than 5 mol%, the extra Sb appears as impurity, and when the doping concentration is lower than 5 mol%, less Sn⁴⁺ could be substituted by Sb⁵⁺. Therefore, the ATO film with 5 mol% of Sb exhibits lower surface roughness and smaller crystallite size.

3.3. Chemical composition analysis

Fig. 5 a shows the XPS survey spectra of both undoped and Sb-doped SnO₂ films, which illustrates the presence of Sn, Sb and O in all ATO thin films. As shown in high magnification XPS spectra of Sn 3d (Fig. 5 b), the binding energies of Sn3d_{5/2} and Sn3d_{3/2} are found at around 486.6 eV and 495.1 eV, respectively; and the separation between their binding energies is equal to 8.5 eV, which confirms the presence of Sn⁴⁺ in all as-prepared thin films [17, 31].

The detailed XPS spectra of Sb 3d and O 1s (Fig. 5 c) confirms the existence of Sb 3d in ATO thin films, where the binding energies of Sb 3d_{5/2} and Sb 3d_{3/2} are located at 531.0 eV and 540.1 eV, respectively.

From Fig. 5 c, the peak at a binding energy of 530–532 eV shows that Sb 3d_{5/2} and O 1s overlap, which is in consistence with the literature [4, 32–35]. The deconvolution XPS peak of Sb 3d_{3/2} is shown in Fig. 5 d and confirms the coexistence of Sb⁵⁺ and Sb³⁺ into SnO₂ lattice sites [15, 17, 32, 35] with Sb³⁺ located on the surface and grain boundaries of ATO films [4, 21, 33]. The high percentage of Sb⁵⁺ contributes to an increase of carrier concentration, therefore a decrease in resistivity of ATO films [30].

3.4. Optical studies

3.4.1. Spectroscopic ellipsometry measurements

Spectroscopic Ellipsometry (SE) is a suitable non-destructive technique to analyze the thickness and optical constants (refractive index and the extinction coefficient) of thin films [35–37].

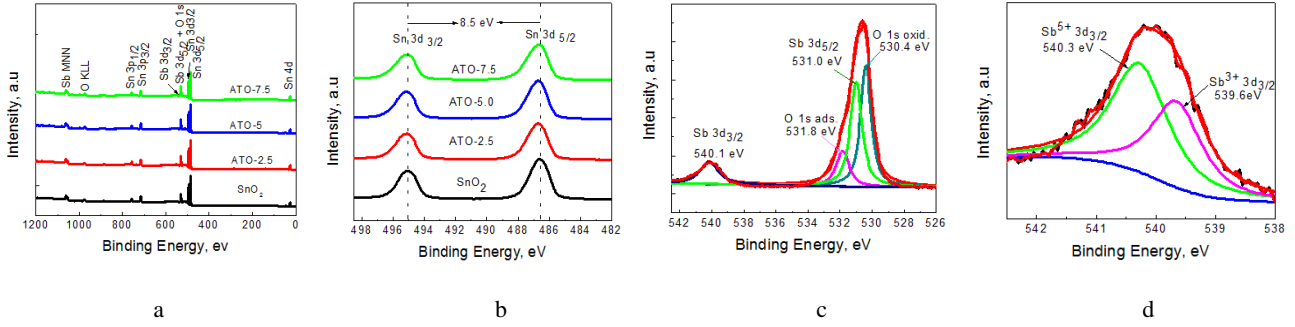


Fig. 5. XPS results of the as-prepared ATO thin films annealed at 500 °C for 1 h: a – survey spectra of all ATO thin films with different Sb-doping concentrations; b – high magnification XPS spectra of Sn 3d for all samples; c – high magnification of O 1s+Sb 3d_{5/2}; d – the deconvolution spectra of Sb 3d_{3/2} for ATO-7.5

The ellipsometric measurements actually yield the ellipsometric parameters Ψ and Δ , which are then simulated using an adequate model fit to extract the optical constants and film thickness [35, 38]. The ellipsometric parameters Ψ and Δ are most often related using the equation [35, 37]

$$\rho = \frac{R_p}{R_s} = \tan \psi \exp(i\Delta), \quad (1)$$

where R_p and R_s are the complex reflection coefficients for light polarized parallel and perpendicular to the plane of incidence, respectively; $\tan \psi$ is the ratio of the amplitude reflection coefficients and Δ is the phase difference between p- and s- polarized waves [35]. To simultaneously determine the optical constants and the film thickness, a uniaxial anisotropic model was built for good fitting of ellipsometric experimental data. To model the ellipsometric data, a Cauchy-Urbach model was first built. After fitting all parameters, some misfits between generated and experimental data were obtained due to thickness non-uniformity. This may be caused by the sol-gel technique, which produces ATO films with uneven and inhomogeneous surfaces. Therefore, a non-uniformity and a uniaxial anisotropy were added to Cauchy-Urbach model. After fitting the parameters from the built model, an appropriate fit between ellipsometric generated and experimental data was obtained accompanied with an improved and acceptable mean-square error (MSE) representing the sum of squares of the differences between generated and experimental data as shown in Table 1; and the final model structure possesses three phases of a uniaxial anisotropic layer describing ATO, the 2.0 nm native oxide of silicon (SiO₂) layer and the Si substrate

layer as illustrated in inset of Fig. 8, Fig. 6 and Fig. 7 illustrate the best fit between the generated and experimental ellipsometric parameters Ψ and Δ in a wavelength range of 400–1700 nm, respectively. After fitting the ellipsometric parameters Ψ and Δ , the determined film thickness was found to decrease with increasing Sb-doping concentration. The thickness decreases from 203.6 nm for undoped SnO₂, to 180.6 nm, 164.5 nm and 152.0 nm for ATO films with 2.5, 5.0 and 7.5 mol% of Sb; respectively, and their comparison with thicknesses determined from SEM cross-section images together with the obtained acceptable mean-square error (MSE) are illustrated in Table 1.

Table 1. The values of thicknesses, MSE and resistivity

Sample	d (SEM), nm	d (SE), nm	MSE	Resistivity, $\Omega \cdot \text{cm}$
SnO ₂	196.1	203.6	12.2	$2.6 \pm 0.01 \times 10^{-1}$
ATO-2.5	180.4	180.6	17.8	$1.6 \pm 0.01 \times 10^{-2}$
ATO-5.0	178.0	168.6	21.5	$1.3 \pm 0.01 \times 10^{-2}$
ATO-7.5	151.8	152.0	61.4	$8.5 \pm 0.01 \times 10^{-3}$

3.4.2. Determination of the optical constants of Sb-doped SnO₂

It is believed that the refractive index and extinction coefficient are important parameters to describe the optical performance of TCO films used in solar cells and other optoelectronic devices. Fig. 8 reveals a clear and distinctive increase in refractive index as the Sb-doping concentration increases in a wavelength range of 400–1700 nm, and the obtained values of n of the as-prepared ATO films annealed at 500 °C for 1 hour vary between 1.54 and 1.77.

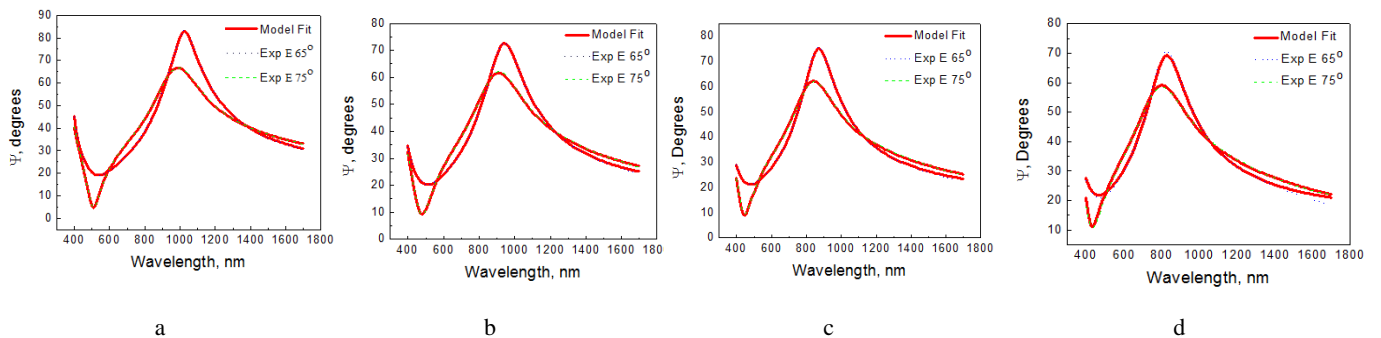


Fig. 6. Measured and generated ellipsometric parameter Ψ of ATO thin films with variation of Sb concentration versus wavelength: a – SnO₂; b – ATO-2.5; c – ATO-5.0; d – ATO-7.5

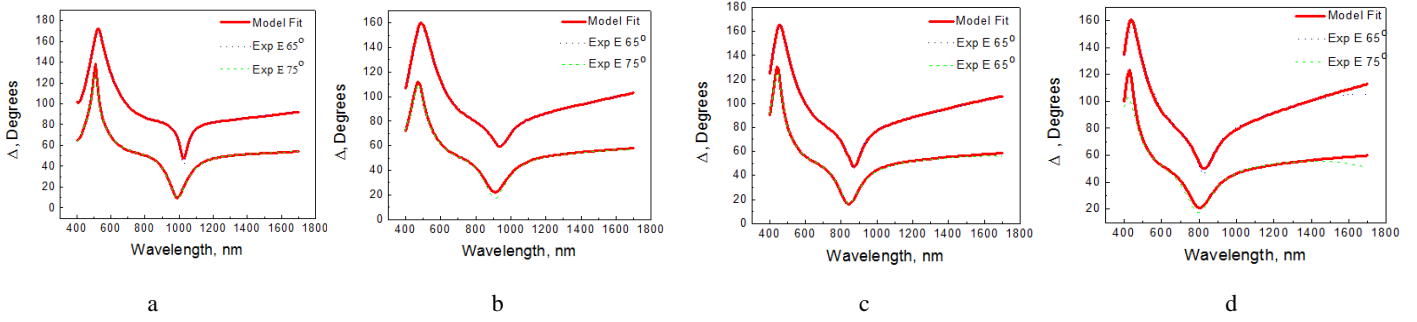


Fig. 7. Measured and generated ellipsometric parameter Δ of ATO thin films with variation of Sb concentration versus wavelength: a – SnO₂; b – ATO-2.5; c – ATO-5.0; d – ATO-7.5

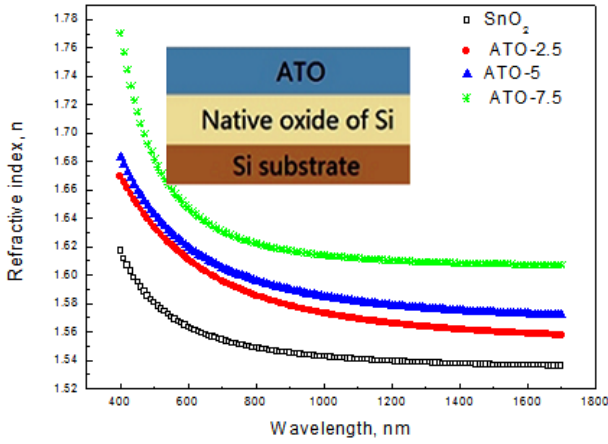


Fig. 8. Variation of the refractive index of undoped and Sb-doped SnO₂ thin films as a function of wavelength. The inset is the layered structure used to model the SE experimental data

Sibel et al. [14] also found the similar phenomenon of increasing refractive index in SnO₂:Sb after Sb incorporation; and Atay et al. [39] prepared SnO₂:F films exhibiting a little increase in values of refractive index of SnO₂:F with increasing F-doping concentration. The change in packing density of films to higher value with Sb incorporation into SnO₂ lattice, may lead to the increase in refractive index [40]. Fig. 9 shows the spectra of extinction coefficients extracted from fitted SE experimental data as a function of wavelength for different Sb-doping concentrations.

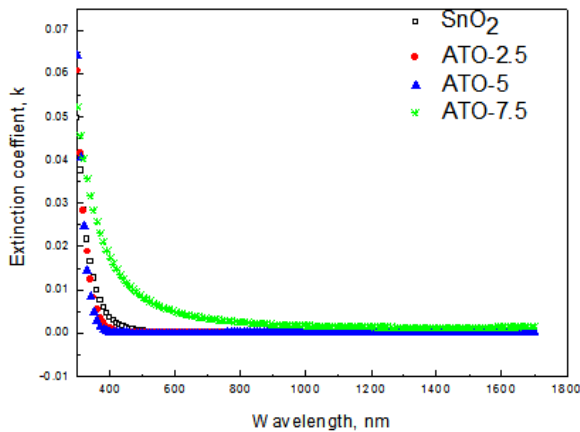


Fig. 9. Variation of the extinction coefficient of undoped and Sb-doped SnO₂ thin films as a function of wavelength ranging between 400 – 1700 nm

The extinction coefficients are extracted in a wavelength range between 400 – 1700 nm, in which the values of extinction coefficients are higher in short wave region and almost zero in visible and near-infrared region; which confirms that both undoped and Sb-doped SnO₂ thin films are transparent in this region. It is clearly seen that the extinction coefficient decreases with increasing Sb-doping concentration up to 5.0 mol% of Sb due to the decrease in crystallite size, whereas it increases for further increase of Sb-doping concentration to a molar ratio of 7.5 mol%, which is in good agreement with XRD results. This decrease in extinction coefficient of ATO films up to 5 mol% of Sb may be due to that the highest level of Sn⁴⁺ is substituted by Sb⁵⁺ and contributes the most electrons in ATO thin films with Sb-doping concentration of 5 mol%.

3.5. Electrical measurements

Fig. 10 illustrates the variation of the electrical resistivity of the films with dopant content, in which, after antimony incorporation into SnO₂ lattice, the resistivity decreases from $2.6 \times 10^{-1} \Omega \cdot \text{cm}$ for undoped SnO₂ to $1.6 \times 10^{-2} \Omega \cdot \text{cm}$, $1.3 \times 10^{-2} \Omega \cdot \text{cm}$ and $8.5 \times 10^{-3} \Omega \cdot \text{cm}$ for SnO₂ thin films doped with 2.5, 5.0 and 7.5 mol% of Sb, respectively. These results are in consistency with the literature that the substitution of Sn⁴⁺ by Sb⁵⁺ leads to a generation of conduction electrons and increase in number of donors facilitating the decrease in electrical resistivity [41, 42], and hence this can enhance the conductivity of the ATO films as well.

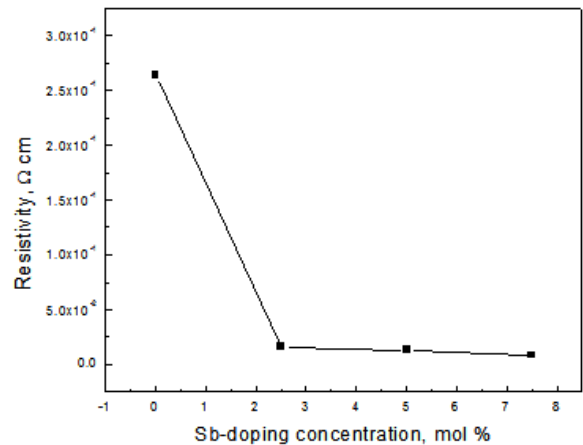


Fig. 10. Variation of resistivity of ATO thin films with Sb-doping concentration

4. CONCLUSIONS

Antimony doped tin oxide (ATO) thin films were prepared via sol-gel spin-coating method and effects of antimony-doping on optical constants, film thickness, resistivity and crystallite size of the ATO thin films are investigated. The surface roughness, extinction coefficient and crystallite size of ATO films decrease with increasing Sb-doping concentration up to 5.0 mol%, while the refractive index increases with increasing Sb. The electrical resistivity decreases with the increase in Sb-doping concentration, and the lowest resistivity obtained at room temperature is found to be $8.5 \times 10^{-3} \Omega \cdot \text{cm}$. By taking into account the obtained values of extinction coefficient and crystallite size together with the surface roughness, the optimum doping concentration for the present ATO films is 5 mol% of Sb.

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